

L Number	Hits	Search Text	DB	Time stamp
1	43697	photoresist and (expos\$4 or unexpos\$4)	USPAT	2003/01/15 15:09
2	11	(photoresist and (expos\$4 or unexpos\$4)) and (uv with (electron adj beam) with plasma)	USPAT	2003/01/15 15:10

L Number	Hits	Search Text	DB	Time stamp
12	321	((((photoresist with expos\$4) and wafer\$4) and (cut\$4 or singul\$4 or dic\$4)) and (photoresist with (silicon or polysilicon))) and (photoresist with deposit\$4)) and (wafer\$4 with (cut\$4 or singul\$4 or dic\$4))	USPAT	2003/01/15 22:21